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(21) International Application Number: PCT/JP99/04660 (22) International Filing Date: 27 August 1999 (27.08.99) (30) Priority Data: 10/244105 28 August 1998 (28.08.98) JP (71) Applicant (for all designated States except US): NITTA CORPORATION [JP/JP]; 4-26, Sakuragawa 4-chome, Naniwa-ku, Osaka-shi, Osaka 556-0022 (JP). (72) Inventors; and (75) Inventors/Applicants (for US only): KAWAHARA, Shinichiro [JP/JP]; Nitta Corporation Nara Factory, 172, Ikezawa-cho, Yamatokooriyama-shi, Nara 639-1085 (JP). KASAZAKI, Toshiaki [JP/JP]; Nitta Corporation Nara Factory, 172, Ikezawa-cho, Yamatokooriyama-shi, Nara 639-1085 (JP). TANI, Naoyuki [JP/JP]; Nitta Corporation Nara Factory, 172, Ikezawa-cho, Yamatokooriyama-shi, Nara 639-1085 (JP). ANDO, Takashi [JP/JP]; Nitta Corporation Nara Factory, 172, Ikezawa-cho, Yamatokooriyama-shi, Nara 639-1085 (JP). YAMAMOTO, Masayoshi [JP/JP]; Nitta Corporation Nara Factory, 172, Ikezawa-cho, Yamatokooriyama-shi, Nara 639-1085 (JP).		(74) Agent: YAMAMOTO, Shusaku; Crystal Tower, 15th floor, 2-27, Shiromi 1-chome, Chuo-ku, Osaka-shi, Osaka 540-6015 (JP). (81) Designated States: KR, SG, US, European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE). Published <i>With international search report.</i> <i>Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</i>
(54) Title: POLISHING CLOTH AND METHOD FOR ATTACHING/DETACHING THE POLISHING CLOTH TO/FROM POLISHING MACHINE BASE PLATE (57) Abstract A polishing cloth includes: a polishing cloth substrate; a first pressure-sensitive adhesive layer formed on a back face of the polishing cloth substrate; a support formed on a back face of the first pressure-sensitive adhesive layer; a second pressure-sensitive adhesive layer formed on a back face of the support; and a release sheet releasably attached to the second pressure-sensitive adhesive layer. The second pressure-sensitive adhesive layer includes an adhesive composition. The adhesive composition contains a pressure-sensitive adhesive and a side-chain crystallizable polymer so that the side-chain crystallizable polymer is present in an amount of about 1 % to about 30 % by weight based on the adhesive composition. The side-chain crystallizable polymer includes as a main component thereof an acrylic acid ester and/or methacrylic acid ester which has a straight-chain alkyl group including 16 or more carbon atoms as a side chain.		